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(71)Applicant : DAICEL CHEM IND LTD

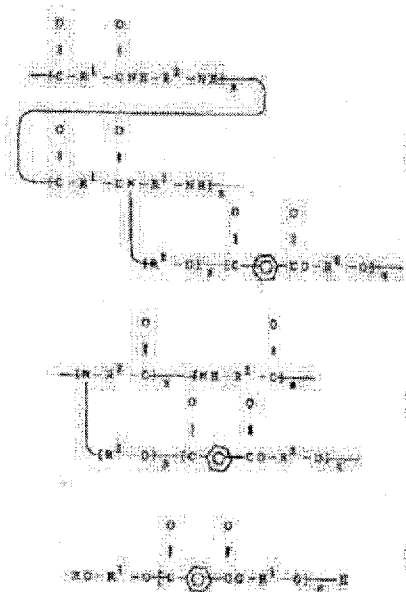
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(72)Inventor : WATANABE ICHIJI

OSAGAWA ICHIRO

NAKADA TATSUYA

(54) HIGH POLYMER BASED ANTISTATIC AGENT



(57)Abstract:

PURPOSE: To obtain a high polymer based antistatic agent consisting of a specific graft polymer and capable of providing excellent antistatic property, gloss, chemical resistance, oil resistance, etc., to a resin for molding without impairing physical properties of the resin for molding by blending with the resin for molding in a proper amount.

CONSTITUTION: An antistatic agent for thermoplastic resin expressed by formula I or formula II [R1 is 4-8C alkylene group or phenylene group which may have a substituent group; R2 is 4-14C alkylene group; R3 is 2-6C alkylene group;

(m) is 1-1000 and (n) is 1-10 and (p) is 1-200 and (g) is integer of 1-500] and composed of a graft polymer in which the trunk polymer is composed of polyamide and the branch polymer is composed of a block polymer of a polyalkylene ether and thermoplastic polyester. The antistatic agent is produced by e.g., reacting a polyamide with 2-4C alkylene oxide in the presence of an alkaline compound to afford a β -hydroxyalkylated polyamide and polycondensing the resultant modified polyamide with a polyester prepolymer of formula III (μ is integer of 1-200).